# **Refractive-Index Behavior of Amorphous Semiconductors and Glasses**

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The refractive-index behavior (magnitude and dispersion) of a variety of optical glasses and amorphous semiconductors is discussed within the same oscillator framework applied earlier to single-crystal refractive-index data. Apart from density differences associated with voids and inefficient packing of disordered atoms, the main quantity of interest turns out to be coordination number as found earlier for single crystals. In tetrahedrally bonded materials  $(SiO_2, Si, Ge, GaP, GaAs, SiO_x)$  the refractive-index behavior, as measured by the dispersion energy  $E_d$ , is not significantly affected by loss of long-range order, lending considerable support to the view that the particular combination of moments of the  $\epsilon_2$  spectrum that determines this oscillator-strength parameter is related solely to short-range interactions. In mixed-oxide glasses the data suggest that admixtures of high-coordination oxides (e.g., BaO or  $La_2O_3$ ) increase the average cation coordination number above 4 and correspondingly increase the strengths of interband optical transitions. Finally, in semiconductors derived from two-dimensional crystals (As<sub>2</sub>S<sub>3</sub>) and one-dimensional crystals (Se and Te) it is found that layer-layer and chain-chain coupling, respectively, increase the effective crystalline coordination number above the nearest-neighbor value and that these interactions are largely lost in the amorphous forms. The primary optical effect is a reduction in oscillator strength of lone-pair to conduction-band transitions and a corresponding decrease in  $E_d$ .

## I. INTRODUCTION

Interest in the optical properties of amorphous semiconductors and glasses has been stimulated by their possible applications as switching elements and optical-transmission media, as well as by their use as passivating materials for integrated circuits. In this paper we will examine the refractive-index behavior (magnitude and dispersion) of several disordered materials and, hopefully, a unified picture will emerge similar in outline to that revealed previously<sup>1</sup> for crystalline solids. Thus, we will focus attention on empirical relationships between refractive indices and the structural and chemical quantities which characterize a material, viz., coordination number and chemical valency. Where possible, comparisons will also be made between amorphous materials and their single-crystal analogs. Finally, we will attempt to relate experimental results to band structure with special attention given to the socalled nonbonded lone-pair valence electrons in such materials as  $As_2S_3$ , Te, and Se.

It should be stressed at the outset that bulk properties of disordered materials are more sensitive to preparation techniques than is the case for single crystals, since imperfections such as voids, microcrystallites, and phase separations are not easily controlled or characterized. For example, amorphous films are often composed of disordered atoms interspersed with voids.<sup>2</sup> The void content, at least in amorphous Ge and Si, is strongly dependent on preparation procedures<sup>2</sup> and can range from about 15% in poorly prepared samples to near zero. In the space between voids there is ample evidence<sup>2</sup> that each atom retains its crystalline tetrahedral coordination but that long-range order is destroyed. The above considerations lead us to suspect that any generalizations deduced about the refractive-index behavior of amorphous solids will turn out to be less precise and less reproducible than corresponding generalizations for single crystals.

Rather than present an exhaustive compilation of experimental data, we concentrate on certain restricted classes of amorphous semiconductors and glasses which are either of current interest or which reveal some particularly interesting aspect of the disordered state. These include (i) optical glasses ranging from fused silica to soda-lime silicate glasses to complex glass systems containing many chemical components (e.g., Pb, Ca, and Ba glasses); (ii) the SiO<sub>x</sub> system where  $0 \le x \le 2$ ; and (iii) the interesting amorphous semiconductors Si, Ge, GaAs, GaP, As<sub>2</sub>S<sub>3</sub>, Te, and Se.

## **II. METHOD OF ANALYSIS**

The analysis presented here follows closely that given earlier<sup>1</sup> for single crystals. Except in a few cases discussed in Sec. IV, where we make use of moments of  $\epsilon_2$  spectra, we focus on fitting refractive-index dispersion data below the band gap to the single oscillator expression

$$n^2 - 1 = \frac{E_d E_0}{E_0^2 - E^2} , \qquad (1)$$

where n is the refractive index for a specified direction of light polarization,  $E_0$  is the energy of the effective dispersion oscillator (typically near

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the main peak of the  $\epsilon_2$  spectrum), *E* is the photon energy, and  $E_d$  is the so-called dispersion energy. The latter quantity measures the average *strength* of interband optical transitions. Its usefulness, which is essentially empirical, rests on the following observations<sup>1</sup> in single crystals.

(i)  $E_d$  is very nearly independent of  $E_0$  and consequently provides an independent oscillatorstrength quantity which does not depend on the energy scale ("band gap") of the fundamental  $\epsilon_2$ spectrum. This contrasts with the commonly used oscillator strength f in the relation

$$n^2 - 1 = \frac{f\Omega_p^2}{E_0^2 - E^2} , \qquad (2)$$

where  $\Omega_{\rho}$  is the plasma frequency of the valence electrons.

(ii)  $E_d$  does not depend on the volume density of valence electrons, i.e., internuclear spacings. This result is in marked contrast to the Phillips-Van Vechten dielectric theory, <sup>3</sup> where both the oscillator-strength quantity  $(\Omega_p^2)$  and the energy-gap parameter  $(E_g)$  depend in prescribed ways on internuclear distances.

(iii) Finally,  $E_d$  obeys a simple empirical relationship in more than 100 widely different ionic and covalent *crystalline* solids, viz.,

$$E_{d} = \beta N_{c} Z_{a} N_{e} \quad \text{eV}, \tag{3}$$

where

$$\beta = 0.37 \pm 0.04 \text{ eV}$$
 (4)

in covalent materials (e.g., C, GaP, ZnS), and

$$\beta = 0.26 \pm 0.03 \text{ eV}$$
 (5)

in the more ionic materials (e.g., NaCl, Al<sub>2</sub>O<sub>3</sub>, T1Br). In Eq. (3),  $N_c$  is the coordination number of the cation nearest neighbor<sup>1</sup> to the anion (e.g.,  $N_c = 6$  in NaCl or ZnWO<sub>4</sub> and  $N_c = 4$  in Ge),  $Z_a$  is the formal chemical valency of the anion (e.g.,  $Z_a=1$  in NaCl,  $Z_a=3$  in GaP, and  $Z_a=2$  in Te), and  $N_e$  is the total number of valence electrons (cores excluded) per anion (e.g.,  $N_e = 8$  in NaCl and Ge,  $N_e = 10$  in T1Cl,  $N_e = 12$  in Te, and  $N_e = 9\frac{1}{3}$  in As<sub>2</sub>S<sub>3</sub>).

Our major purpose will be to examine the validity of Eqs. (3)-(5) in disordered solids. It is clear that the coordination number  $N_c$  will be central to our discussion, although we should not assume *a priori* that crystalline and amorphous forms of a material necessarily exhibit the same nearestneighbor coordination. In order to account for voids we use the simplest possible model and assume that voids reduce the average density without affecting the nearest-neighbor coordination in the filled spaces between voids. On the average, however, there may be some small reduction in  $N_c$  associated with incomplete or dangling bonds at void boundaries. The primary effect of voids is a reduction in density, and consequently we scale  $E_d$ , which is proportional to  $\epsilon_2$ , by the crystallineto amorphous-density ratio before drawing conclusions about coordination number. The above considerations are summarized in the proposed relation

$$E_{d}^{a}/E_{d}^{x} = (\rho^{a}/\rho^{x}) \left(N_{c}^{a}/N_{c}^{x}\right), \qquad (6)$$

where  $\rho$  is the density, and *a* and *x* refer to amorphous and crystalline forms, respectively.

## **III. EXPERIMENTAL RESULTS**

## A. Optical Glasses

We begin this section with a detailed discussion of fused silica  $(SiO_2)$  partly because it is a simple chemical system and partly because refractiveindex data are available for the single-crystal analog (quartz). The fused silica results have been obtained from the recent index data of Waxler and Cleek.<sup>4</sup> Room-temperature parameter values are given in Table I along with corresponding values in crystalline quartz for both ordinary ray  $(n_0)$  and extraordinary ray  $(n_e)$  refractive indices. Average values of  $E_0$  and  $E_d$  are also tabulated. The value  $E_d = 18.1$  eV for crystalline quartz compares with an average  $E_d = 18.0$  eV in four other four-coordinated ionic oxides.<sup>1</sup> Note in particular that the oscillator position  $E_0$  is almost exactly the same in both the glassy and crystalline forms. a result that is evident in the uv-reflectivity results of Philipp.<sup>5</sup> Philipp also finds, apart from a small amount of broadening in fused silica. that the detailed structure in the uv-reflectivity spectra of the two materials is identical, leading to the conclusion that optical properties of the SiO<sub>2</sub> system are determined by the  $SiO_4$  tetrahedra and that long-range order is of little consequence. The interband transition strengths, on the other hand, are considerably different with  $E_d = 14.71$  eV in fused silica, a value 19% smaller than in crystalline quartz. It should be noted, however, that the density of fused silica is 17% smaller than crystalline quartz even though the Si-O distance remains essentially the same ( $\approx 1.62$  Å). It is tempting, therefore, to attribute the smaller oscillator strength in the disordered form simply to inefficient packing of  $SiO_4$  tetrahedra. Although not easily proved, the ex-

TABLE I. Dispersion parameters for fused and crystalline  $SiO_2$ . Values of  $\beta$  from Eq. (3) are also given.

	$E_d$ (eV)	$E_0$ (eV)	β (eV)
Fused SiO <sub>2</sub>	14.71	13.38	0.23
Crystal SiO <sub>2</sub> (avg)	18.10	13.33	0.28
Crystal SiO <sub>2</sub> $(n_0)$	18.04	13.37	•••
Crystal SiO <sub>2</sub> $(n_e)$	18.22	13.25	•••

tra 2% reduction in  $E_d$  not accounted for by the density decrease may be due to incomplete or dangling bonds characterized by an average Si coordination number slightly less than 4. Robinson<sup>6</sup> has discussed the structure of fused silica in considerable detail and proposes a pentagonal-dodecahedral model which partially fills the volume with a distorted array of SiO<sub>4</sub> tetradedra, although some Si atoms are incompletely bonded to oxygen. The randomness is primarily contained in variations of the Si-O-Si angles associated with distortions of the SiO<sub>4</sub> tetrahedra.

Although the above results suggest that disordered and crystalline forms of  $SiO_2$  are virtually indistinguishable optically when packing-density effects are taken into account, examination of the temperature dependence of the refractive index reveals substantial differences. We can examine the thermo-optic behavior by using Eq. (1) with temperature-dependent parameters  $E_d$  and  $E_0$ . In differential form Eq. (1) becomes

$$\frac{dn}{dT} = -\frac{(n^2 - 1)^2}{2n} \left(\frac{dE_0}{dT} / E_d\right) \times \left((1 - K) + \frac{(1 + K)E^2}{E_0^2}\right), \quad (7)$$

where

$$K = \frac{d \ln E_d}{dT} \bigg/ \frac{d \ln E_0}{dT} \quad . \tag{8}$$

Values of  $dE_0/dT$  and K are given in Table II for fused silica at 293 and 73  $^{\circ}$ K and for crystalline quartz at 295 °K. The quantity K depends in a rather subtle way on the detailed shape (and its temperature dependence) of the  $\epsilon_2$  spectrum. Thus, for a linear energy shift with temperature of the entire  $\epsilon_2$  spectrum without distortion, it can be shown that  $0 \leq K \leq 1$ . The precise value depends on details of the spectral shape. For K > 1, it is necessary that the  $\epsilon_2$  spectrum change shape as well as shift position with temperature. The value K = 1 also forms a boundary between situations where the magnitude of dn/dT increases (K < 1) or decreases (K > 1) as the photon energy approaches the interband edge. The latter situation also allows for a change in sign of dn/dT as a function of optical wavelength.

Returning to Table II, we note that K > 1 in crystalline quartz and K < 1 in fused SiO<sub>2</sub>. There is also a strong temperature dependence of K in fused silica, although  $dE_0/dT$  is independent of temperature to 73 °K. With respect to the "bandgap" temperature dependence, values of  $dE_0/dT$  in the two forms of SiO<sub>2</sub> are very similar to magnitudes typical of most solids. It is of interest to note that the larger value of  $dE_0/dT$  in fused silica is associated with a very small coefficient of thermal expansion (0. 5×10<sup>-6</sup> °C<sup>-1</sup>), when compared with crystalline quartz  $(11 \times 10^{-6} \circ C^{-1})$ . It would appear that thermal expansion has very little influence on the thermooptic behavior of these materials. Much more subtle effects associated with thermal broadening dominate.

In conclusion, we have shown that gross features of the refractive-index behavior of crystalline and disordered forms of  $SiO_2$  are essentially identical when the inefficient packing of atoms in the glassy form is taken into account, while more subtle differences are revealed by comparison of their thermo-optic behavior.

We now ask if other oxide glasses exhibit similarities with fused SiO<sub>2</sub>; that is, are they simply loosely packed four-coordinated oxides with values of  $E_d \approx 15$  eV and composition-dependent band gaps? Experimental results for a limited assortment of glasses<sup>7,8</sup> are given in Table III. Inspection of Table III leads to the following conclusions.

(i) Apart from the rare-earth glasses [Table III (h)] and very high-Pb glasses [Table III (g)] values of  $E_d$  (15.5±10% eV) are very similar to the value found in fused quartz (14.71 eV).

(ii) The optical band gap decreases on addition of other oxides to  $SiO_2$  with the effect increasing in the order CaO, BaO, Na<sub>2</sub>O, PbO.

(iii) The optical-transition strengths decrease slightly with the addition of  $Na_2O$  but increase somewhat on addition of BaO, CaO, and PbO, with the largest rate of increase occurring for BaO and the smallest for PbO.

(iv) Values of  $E_d$  in the La containing glasses<sup>8</sup> (composition unknown) are considerably higher (19, 6-21, 2 eV) than in the other glasses.

Although a detailed understanding of the trends noted above would require unavailable structural information, we suggest, tentatively, that the observed increase in  $E_d$  with additions of BaO, CaO, PbO, and La<sub>2</sub>O<sub>3</sub> is primarily a coordination-number effect; that is, all these cations prefer coordination numbers higher than four. For example, single-crystal BaO, CaO, and PbO are all sixcoordinated oxides, while La<sub>2</sub>O<sub>3</sub> is seven coordinated. In large groups of six-coordinated *crystalline* oxides, we find<sup>1</sup> that  $E_d = 25 \pm 2$  eV, compared with  $E_d \approx 18$  eV in several four-coordinated oxides, so that it is not unreasonable to suspect

TABLE II. Thermo-optic parameters for fused and crystalline  $SiO_2$  [see Eqs. (7) and (8)].

$\frac{dE_0}{dT}$ (10 <sup>-4</sup> eV/°C)	K	
-5.4	+0.43	
-5.4	+0.83	
-3.9	+1.45	
-4.7	+1.47	
	$\frac{dE_0}{dT} (10^{-4} \text{ eV/}^\circ\text{C}) \\ -5.4 \\ -5.4 \\ -3.9 \\ -4.7 \end{cases}$	

TABLE III. Dispersion parameters for assorted oxide glasses.

(a) $100 \text{SiO}_2 \times x \text{Na}_2 \text{O}$			(b) $100 \text{SiO}_2 \times 20 \text{Na}_2 \text{O} \times x \text{PbO}$			
x	E	$\mathcal{E}_d$ (eV)	$E_0$ (eV)	x	$\tilde{E_d}$ (eV)	$E_0 (eV)$
0		14.71	13.38	0	14.4	11.9
20		14.4	11.9	5	14.3	11.0
30		14.5	11.7	10	14.1	10.2
40		14.4	11.5	20	14.6	9.6
70		14.2	11.1	30	14.6	8.9
100	:	14.1	10.8	40	15.0	8.7
(c)	100Si	$O_2 \times 20 K_2 O \times$	x PbO	(d) 100	$SiO_2 \times 20Na$	$_{2}O \times xCaO$
x	E	$C_d$ (eV)	$E_0$ (eV)	x	$E_d$ (eV)	$E_0$ (eV)
0	:	14.7	11.9	0	14.4	11.9
5	1	14.1	10.8	5	14.8	12.0
10	1	14.2	10.2	10	15.0	11.8
20	1	14.5	9.5	20	15.5	11.7
30	1	14.5	8.9	30	15.9	11.6
40	1	14.9	8.6	40	15.8	11.4
(e) $100 \text{SiO}_2 \times 20 \text{Na}_2 \text{O} \times x \text{BaO}$		(f) $100 \text{SiO}_2 \times 10 \text{Na}_2 \text{O} \times 10 \text{K}_2 \text{O} \times x \text{BaO}$				
x	E	$_{d}$ (eV)	$E_0$ (eV)	x	$E_d$ (eV)	$E_0$ (eV)
0	1	4.4	11.9	5	15.0	11.9
5	1	4.7	11.7	10	15.2	11.7
10	15.3		11.7	20	15.8	11.4
20	16.0		11.5	30	16.4	11.3
30	1	7.0	11.2	40	16.8	11.1
(g) $100 \text{SiO}_2 \times x \text{PbO} \times v \text{K}_2 \text{O}$			(h) Rare-earth glasses (Schott)			
x	У	$E_d$ (eV)	$E_0$ (eV)		$E_d$ (eV)	$E_0$ (eV)
0	0	14.71	13.38	LaKN14	21.2	11.7
10	20	14.2	10.2	LaFN2	20.3	10.4
20	20	14.5	9.5	LaSFN3	19.6	9.1
<b>4</b> 0	5	15.3	8.5			
50	9	15.5	8.0			
70	13	16.2	7.6			
95	0	17.4	6.9			
.23	0	18.3	6.4			

that the observed range of  $E_d$  in the listed oxide glasses (14. 1-21. 2 eV) is primarily a consequence of variations in average cation coordination number. The rare-earth ions, as expected, are the most effective in increasing coordination number whereas PbO is the least effective. Of course, there may also be some undetermined variations in  $E_d$  associated with differences in the microstructure and void content (density) of the different glass compositions, although such effects, if present, are not easily elucidated in the absence of detailed structural information.

In summary, variations in the refractive behavior of oxide glasses can be understood as arising principally from changes in the band gap with composition. The relatively small transitionstrength changes that do occur, particularly in the rare-earth glasses, are probably a result of differences in the average cation coordination number.

It is of interest to reexamine the dispersion behavior of the oxide glasses from the point of view of lens designers, in light of the trends outlined above. Historically,<sup>9</sup> dispersion has been measured using the reciprocal dispersive power (or Abbe value)  $\nu$  defined by

$$\nu = (n_D - 1)/(n_F - n_C) , \qquad (9)$$

where  $n_D$ ,  $n_F$ , and  $n_C$  refer to refractive indices at 5890, 4861, and 6563 Å, respectively. It is easy to show using Eq. (1) that

$$\nu = 0.72E_0^2 [n_D / (n_D + 1)] \tag{10}$$

 $\mathbf{or}$ 

$$\nu = 0.72E_d^2 (n_{\infty}^2 - 1)^2 [n_D / (n_D + 1)] . \qquad (11)$$

In Eq. (11)  $n_{\infty}$  is the long-wavelength extrapolation. According to Eq. (10), the Abbe value depends almost exclusively on the band gap  $E_0$  since the refractive-index factor changes only from 0.58 to 0.67 as  $n_D$  varies from 1.4 to 2.0. We have plotted Eq. (11) in Fig. 1 for several values of  $E_0$  by taking  $n_{\infty} \approx n_D = n$ . The top scale gives the band gap from Eq. (10) with  $n_D/(n_D + 1) = 0.63$ . The field of existing colorless optical glasses shown in the figure clearly reveals the inherent limitations imposed by available band gaps and transition strengths. The lower boundary in the figure as well as the tail for  $\nu > 80$  occurs in glasses containing fluorine. Fluorides are known<sup>1</sup> to exhibit smaller values of  $E_d$  and larger band gaps than oxides. Because oxides are limited in band gaps to about 13 eV, values of  $\nu > 80$  must necessarily occur in nonoxide systems. The increase in the upper boundary shown in the figure for  $\nu < 80$ merely reflects the lower band gaps occurring in glass-forming oxides that prefer coordination numbers above four. We can conclude that existing oxide glasses essentially exhaust the obtainable ranges of n and  $\nu$  (i.e.,  $14 < E_D < 23$  eV and  $E_0 < 13$  eV). It is of interest that liquids tend to have lower values of  $E_d$  than solids<sup>1</sup> (e.g.,  $E_d \approx 11$ eV in CCl<sub>4</sub> and CS<sub>2</sub>) suggesting, according to Fig. 1, that  $\nu$  will be smaller for a given value of  $n_{\bullet}$ 

### B. Disordered SiO, System

Use of  $SiO_x$  and SiO films for passivating and protective layers has prompted some recent interest in their optical properties. For example, Philipp<sup>5</sup> has shown that the above gap reflectivity data can be understood in terms of a microscopic distribution of Si-Si and Si-O bonds and that these bonds exhibit optical properties very similar to those observed in the amorphous-end members Si and  $SiO_2$ . He also suggests that short-range order primarily determines the optical properties. In order to interpolate the optical dielectric constant between Si and  $SiO_2$ , Philipp proposes the following form:

$$\epsilon_{\mathrm{SiO}_{\mathbf{x}}} \approx \left(1 - \frac{1}{2}x\right)^2 \epsilon_{\mathrm{Si}} + \left(\frac{1}{2}x\right) \epsilon_{\mathrm{SiO}_{\mathbf{y}}}, \qquad (12)$$

where  $\epsilon_{si}$  and  $\epsilon_{sio2}$  are the optical dielectric constants of amorphous Si and SiO<sub>2</sub>, respectively, and the quadratic term is an attempt to account for the fact that both the absorption-edge position and absorption strength change with increasing Si con-



FIG. 1. Refractive index as a function of reciprocal dispersive power  $\nu$  and oscillator energy  $E_0$  for various values of  $E_d$ . The shaded area to the right of  $\nu = 14$  gives the field of existing colorless optical glasses, while glasses with  $\nu < 14$  would be colored and have been omitted from discussion.

tent. A simple interpolation scheme that falls within the context of the present article would involve *linear* interpolation between the end-member values of  $E_0$  and  $E_d$ . Thus, using the values for fused silica shown in Table I and the values  $E_d$ = 38.6 eV and  $E_0$ = 3.68 eV for amorphous Si we assume that

 $E_d(\text{SiO}_x) = 38.6(1 - \frac{1}{2}x) + 14.7(\frac{1}{2}x)$ 

and

$$E_0(\mathrm{SiO}_x) = 3.68(1 - \frac{1}{2}x) + 13.38(\frac{1}{2}x) . \tag{14}$$

The resulting long-wavelength refractive index  $n^2 = 1 + E_d / E_0$  is plotted versus x in Fig. 2. The indicated points are taken from the reflectivity data of Philipp.<sup>5</sup> Agreement is fair considering that the actual composition for the x = 1.5 point was not accurately known, although no error bars were given.

#### C. Amorphous Semiconductors

In this section we examine the refractive-index behavior of a few amorphous semiconductors of current interest. Values of  $E_d$  and  $E_0$  are given in Table IV along with averages for the crystalline forms. The result for amorphous Si is difficult to analyze in detail because no accurate density information is available for the films used in the measurements, although it should be noted that Chittick<sup>10</sup> reports an approximate density decrease in the amorphous films of  $18\% \pm 6\%$ , which at least overlaps the observed 13% decrease in  $E_d$ . Moss and Graczyk<sup>13</sup> find a density decrease of 10-15%, while Brodsky and Stiles<sup>2</sup> have discussed available

TABLE IV. Dispersion parameters and densities  $(\rho)$  for several amorphous and crystalline semiconductors.

ρ		$E_d$ (eV)	$E_0$ (eV)	Ref.
•••	amorphous Si	38.6	3.7	a
2.33	crystal Si	44.4	4.0	b
5.82	amorphous Te	16	1.4	с
6.25	crystal Te (avg)	37	1.3	d
4.29	amorphous Se	18.6	3.9	е
4.81	crystal Se (avg)	33	3.8	f
3.20	amorphous As <sub>2</sub> S <sub>3</sub>	22.8	4.7	g
3.42	crystal As <sub>2</sub> S <sub>3</sub> (avg)	27	4.5	ĥ

<sup>a</sup>See Ref. 10.

(13)

<sup>b</sup>W. Primak, Appl. Opt. <u>10</u>, 759 (1971).

<sup>c</sup>See Ref. 11.

<sup>d</sup>S. Singh, *Handbook of Lasers* (The Chemical Rubber Co., Cleveland, 1971), pp. 489-507.

<sup>e</sup>W. F. Koehler, F. K. Odencrantz, and W. C. White, J. Opt. Soc. Am. <u>49</u>, 109 (1959).

<sup>f</sup>I. Gampel and F. J. Johnson, J. Opt. Soc. Am. <u>59</u>, 72 (1969).

See Ref. 12.

<sup>h</sup>B. L. Evans and P. A. Young, Proc. Roy. Soc. (London) <u>A297</u>, 230 (1967).



FIG. 2. Refractive index as a function of x for the amorphous system  $SiO_x$ . The points are taken from Ref. 5.

density information and conclude that the decrease is near 13%. They also conclude that approximately 10% of this decrease is due to voids and the remaining 3% results from inefficient packing of atoms in the "filled" space between voids. The above results suggest that the observed reduction in  $E_d$  may be a simple density effect as noted earlier for SiO<sub>2</sub>; however, more definite conclusions must await refractive-index dispersion and accurate density measurements on the same film.

The chalcogenide materials listed in Table IV are somewhat more interesting. In the case of Te and Se there is nearly a factor of 2 decrease in  $E_d$  in going from crystalline to amorphous forms. The measured  $\epsilon_2$  spectra<sup>11</sup> also show a factor of 2 decrease in the vicinity of  $E_0$ . In the case of As<sub>2</sub>S<sub>3</sub> the decrease is only 16% again in approximate agreement with  $\epsilon_2$  spectra.<sup>14</sup> Another point of interest is the slightly larger band gaps in the amorphous forms of all three materials. In order to relate the  $E_d$  data to Eq. (3), it is necessary to consider the crystal structure (coordination number). Crystalline (class 32) Te and Se con-

sist of spiral chains of atoms bonded covalently with a nearest-neighbor coordination of two. Adjacent parallel chains are more weakly bonded to one another. Similarly, As<sub>2</sub>S<sub>3</sub> consists of twodimensional layers in which the As coordination number is three. Bonding between layers is relatively weak. If we assume that  $N_c = 2$ ,  $Z_a = 2$ , and  $N_e = 12$  in Te and Se and  $N_c = 3$ ,  $Z_a = 2$ ,  $N_e = 9\frac{1}{3}$  in As<sub>2</sub>S<sub>3</sub>, we find that  $\beta$ (Te) = 0.77 eV,  $\beta$ (Se) = 0.69 eV, and  $\beta(As_2S_3) = 0.48$  eV. These  $\beta$  values are all substantially larger than observed in other covalent crystalline solids, viz.,  $\beta = 0.37 \pm 0.04$ eV. There is considerable evidence, however, that this discrepancy lies in our choice of too small a coordination number  $N_c$ . For example, Levine<sup>15</sup> finds that it is necessary to take  $N_c \approx 4$  in Te and Se in order to fit these materials into the widely applicable Philipps-Van Vechten dielectric theory.<sup>3</sup> Furthermore, Hulin<sup>16</sup> as well as Gissler et al.<sup>17</sup> have shown that the interaction of a given atom with the four next-nearest neighbors on adjacent chains, when compared with the two nearest neighbors in the same chain, is only about a factor of  $2 \text{ smaller}^{18}$ 

TABLE V. Summary of effective coordination numbers in amorphous and crystalline forms of three semiconductors.

	Crystal	Amorphous	Nearest-neighbor $N_c$		
$As_2S_3$	3.6	3.2	3		
Те	4.0	2.1	2		
Se	3.3	2.2	2		

in Te and a factor of  $3 \text{ smaller}^{18}$  in Se. Thus we might speculate that the effective coordination number is about  $2 + \frac{4}{2} = 4$  in Te and  $2 + \frac{4}{3} = 3.3$  in Se. Using these values for  $N_c$ , we find that  $\beta(\text{Te})$  $\approx 0.39 \text{ eV}$  and  $\beta(\text{Se}) \approx 0.41 \text{ eV}$ , in agreement with other covalent materials and in essential agreement with one another. In the case of crystalline As<sub>2</sub>S<sub>3</sub>, we require  $N_c \approx 3.6$  rather than  $N_c = 3$  in order to fit this material into the general covalent picture with  $\beta \approx 0.4$  eV. A value  $N_c > 3$  is not surprising in view of the octahedral coordination of those As atoms which "bond" the layers together. <sup>19</sup> Within our present model, the above value of  $N_c$ suggests that about 20% of the As atoms act as bonding points between layers. The relatively modest increase in  $N_c$  above 3 for crystalline As<sub>2</sub>S<sub>3</sub> implies that interactions between layers in As<sub>2</sub>S<sub>3</sub> are much weaker than chain-chain interactions in Te and Se. Finally, we should point out other independent evidence that non-nearest neighbors can influence  $E_d$  under special circumstances. In the case of solid  $H_2O$  (ice) each cation (H<sup>+</sup>) is surrounded by two oxygen atoms at distances of 1.0 and 1.7 Å. Using  $E_d = 8.7$  eV and taking  $Z_a$ = 2 and  $N_e = 8$ , we find that  $\beta = 0.54$  eV for  $N_c = 1$ and  $\beta = 0.27$  eV for  $N_c = 2$ . These values bracket the covalent value of 0.37 eV and suggest a nonintegral effective proton coordination number of about 1.5 in ice.

Turning now to results for the amorphous forms listed in Table III, it is necessary first to normalize out any density differences between the disordered materials and their single-crystal analogs. Thus amorphous As<sub>2</sub>S<sub>3</sub> is only 7% less dense<sup>20</sup> than crystalline  $As_2S_3$  while  $E_d$  is about 16% smaller. The extra 9% reduction may result from a small decrease in the effective As coordination number (from  $N_c \approx 3.6$  to  $N_c \approx 3.2$ ) due to a reduction in the number of octahedral bonding points between layers by roughly a factor of 3. The value for amorphous As<sub>2</sub>S<sub>3</sub> is not very different from that reported by Varpolin and Porai-Koshits<sup>19</sup> using x-ray radial-distribution analyses. A similar argument can be given for amorphous Te and Se. The 57% decrease in Te includes a contribution of only about 9% due to the density decrease, <sup>21</sup> while only 11% of the total 44% decrease in Se is due to density.<sup>21</sup> We suggest that the remaining large

decrease in  $E_d$  in Te (48%) and in Se (33%) is due to reduced interaction between chains<sup>11</sup> in the amorphous forms and a consequent tendency for  $N_c$  to approach the single isolated chain value of 2. Using this model we find that  $N_c \approx 2.1$  in amorphous Te and  $N_c \approx 2.2$  in amorphous Se. The above results are summarized in Table V. Apart from trivial density factors, the amorphous forms of these materials differ from their crystalline analogs, within the present model, because interchain coupling is weakened in the case of Te and Se, and interlayer coupling is weakened in As<sub>2</sub>S<sub>3</sub>. Futhermore, we would suggest that all these materials fall into the same general covalent framework described by Eqs. (3) and (4) with  $\beta \approx 0.4$  eV.

#### IV. ENERGY-BAND CONSIDERATIONS

In the foregoing presentation we have concentrated on essentially three classes of amorphous solids, viz., ionic oxides (SiO2), covalent materials bonded with directed  $sp^3$  tetrahedral bonds (Si). and covalent materials containing unshared (lonepair) electrons (Te, Se, As<sub>2</sub>S<sub>3</sub>). The latter situation has been discussed recently by Kastner.<sup>22</sup> Figure 3 shows schematic energy-level diagrams for these three types of solids. For purposes of comparison, we have forced the energy gaps to be equal. Note that the valence s states lie far below the top of the valence band in  $SiO_2$  and Se, and that the band edge in Se involves transitions between lone-pair p states and antibonding conduction-band states. With these distinctions in mind it is of interest to compare published<sup>2,5,11,14</sup>  $\epsilon_2$  spectra for these different classes of materials in both their crystalline and disordered forms. The experimental results are presented in Figs. 4-6 for SiO<sub>2</sub>, Si, and Se. The principal feature of the  $SiO_2$  data, as noted earlier, is the presence of the same sharp structure in both crystalline and disordered forms. We have, in fact, omitted the data for amorphous  ${\rm SiO}_2$  in Fig. 4 since the curve closely mirrors the crystalline results lowered in magnitude by about 20%. It is clear that loss of long-range order has only mildly affected the optical properties and that "localized" excitonic transitions involving individual SiO<sub>4</sub> tetrahedra must dominate. This very simple situation is certainly related to the relatively ionic character of  $SiO_2$ . In the case of covalent silicon, sharp structure associated with long-range order found in the single-crystal data is essentially averaged out in the amorphous material, with the resulting  $\epsilon_2$  spectrum being more or less a smoothed version of the single-crystal result shifted to lower energy and reduced in magnitude.

The Si results noted above are very much like those reported for amorphous Ge by Donovan  $et \ al.^{23}$  and for six amorphous III-V compounds



by Stuke and Zimmerer.<sup>24</sup> It is of interest to compute  $E_d$  for these other materials from published  $\epsilon_2$  spectra using the moment relation<sup>1</sup>

5

€2 1.0

0.5

0.2

0.1

0

 $E_{\rm d}^{\rm 2}=M_{\rm -1}^{\rm 3}/M_{\rm -3}\;, \label{eq:eq:entropy}$  where the rth moment  $M_{\rm r}$  is defined by



10

E(eV)

15

20

\_\_\_\_\_

FIG. 4. Loss part of dielectric function for crystalline  $SiO_2$ (Ref. 5). The curve for amorphous  $SiO_2$  essentially mirrors this curve about 20% lower in magnitude.

(15)



FIG. 5. Loss part of dielectric function for crystalline and amorphous Si (Ref. 2).

$$M_r = (2/\pi) \int_{E_g^*}^{\infty} E^r \epsilon_2(E) dE; \qquad (16)$$

E is the photon energy and  $E_g$  is the band gap. Results are given in Table VI. We have omitted InP, GaSb, InSb, and InAs from the tabulation because plots of  $\epsilon_2/E^3$  vs E for these materials show a lack of convergence at low energies resulting, presumably, from experimental errors. In low-band-gap materials, the moment  $M_{-3}$  is very sensitive to the values of  $\epsilon_2$  near the gap. Returning to Table VI, we note that the value  $E_a \approx 34 \text{ eV}$  obtained from the  $\epsilon_2$  spectrum of amorphous Si is somewhat less than the value  $E_d = 38.6$ eV obtained from refractive-index dispersion data on different films (see Table IV). A more detailed comparison cannot be made at present because precise density information is not available. It is possible, perhaps, that the surface oxide contamination on Si described recently by Philipp<sup>26</sup> affects the reflectivity data and contributes to the low value of  $E_d$ . More definite conclusions are

possible for amorphous Ge. The low-density (87% of crystalline) films<sup>22</sup> deposited at room temperature yield a value  $E_d = 35 \text{ eV}$  which, when corrected for density, give  $E_d = 40 \pm 1$  eV compared with  $E_d$ = 41 eV in crystalline Ge. In films<sup>23</sup> deposited at 250-300 °C, <sup>25</sup> the absorption edge is shifted upward from 0.6 to 0.8 eV resulting in a lower value of  $M_{-3}$ , and the density is near that of crystalline Ge. For this material  $E_d = 39 \pm 1$  eV, which is very close to the crystalline value. Similarly, for both  $GaP^{24}$  and  $GaAs^{24}E_d = 34$  eV in their amorphous forms, but density corrections yield  $E_{d}$ =  $37 \pm 3$  eV nicely overlapping the crystalline values of 37 eV. Note, however, the very large reduction in  $E_0$  in amorphous GaP when compared with GaAs, Ge, or Si. The above results lend considerable support to the view that  $E_d$  is a measure of oscillator strength that is largely independent of the long-range order in tetrahedral diamond-type compounds. The  $\epsilon_2$  spectrum changes its shape and magnitude so as to keep  $E_d$  constant, and in particular this requires smaller peak values of  $\epsilon_2$  in amorphous material if the band gap is shifted to lower energy.

A qualitatively different situation from that in Si and Ge exists in Se (and also in Te and  $As_2S_3$ ), where the two main peaks at 4 and 8 eV are preserved in amorphous material, but the strength of the lower-energy peak markedly decreases. This peak is associated<sup>22</sup> with transitions between filled lone-pair p states and empty antibonding pstates (see Fig. 3). Within the framework of our coordination model, we would conclude that the strengths of these lone-pair transitions depend rather strongly on interchain and interlayer coupling, whereas their energy positions are relatively independent of these interactions. Some experimental support for this view is provided by the photoelastic data of Galkiewicz and Tauc,<sup>12</sup> who find that the quantity  $K = d \ln E_d / d \ln E_0 \approx 44$  in amorphous  $As_2S_3$ , where the indicated fractional changes are associated with pressure-induced dilatation. Thus, transition strengths are much more strongly affected by strain in this material than transition energies. For comparison it should be noted that  $K \approx -0.51$  in GaAs.<sup>12</sup>

TABLE VI. Summary of dispersion parameters obtained using moments of  $\epsilon_2$  spectra.

	Amorphous		Crystalline			
	$\rho^{a}/\rho^{x}$	$E_d$ (eV)	$\boldsymbol{E}_0~(\mathrm{eV})$	$E_d$ (eV)	$E_0$ (eV)	Ref.
Si	•••	34	3.1	44.4	4.0	2
Ge	$0.87 \pm 0.02$	35	2.3	41	2.7	23
Ge	$1.0 \pm 0.03$	39	2.6	41	2.7	25
GaP	0.85-1	34	3.1	36.8	4.6	<b>24</b>
GaAs	0.85-1	34	2.9	36.7	3.7	24



FIG. 6. Loss part of dielectric function for crystalline and amorphous Se (Ref. 11).

# **V. CONCLUSIONS**

We have suggested that the refractive-index behavior of amorphous solids can be understood within the same general framework established earlier for crystalline solids with the same value of  $\beta$ . Apart from important, though not always reproducible, density differences associated with inefficient packing of disordered atoms, the main quantity of interest is coordination number. In tetrahedrally bonded materials, whether ionic  $(SiO_2)$  or covalent (Ge), the results indicate that the refractive-index behavior, as measured by the dispersion energy  $E_d$ , remains largely unaffected by loss of long-range order. That is, the nearestneighbor environment remains largely intact, and it is this environment which dominates the optical properties. In the mixed oxide glass systems we suggest that the observed variations in transition strengths  $E_d$  result primarily from changes in the

average nearest-neighbor coordination number produced by admixtures of high-coordination oxides (e.g., BaO or  $La_2O_3$ ). Finally, in two-dimensional crystals ( $As_2S_3$ ) and one-dimensional crystals (Te and Se), it is proposed that layer-layer and chain-chain bonding, respectively, increase the effective coordination number above the nearestneighbor value and that these interactions are effectively lost, or at least greatly reduced, in the amorphous forms. The primary optical effect is a reduction in oscillator strength of lone-pair to conduction-band transitions.

## ACKNOWLEDGMENTS

The author wishes to thank Professor J. Tauc for informative discussions on the optical properties of amorphous semiconductors and M. DiDomenico, Jr. and S. Knight for helpful comments on the manuscript.

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15 APRIL 1973

# Electronic Properties of an Amorphous Solid. III. The Cohesive Energy and the Density of States\*

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The effect of topological disorder on the cohesive energy and the electronic density of states of amorphous Si and Ge is investigated. The methods used include moment expansions and various exactly soluble models that include the Bethe lattice and Husimi cactus lattices, for which an extremely compact derivation of the density of states is presented. An isolated topological defect in a diamond cubic lattice is also studied. The question of the existence of square-root band edges in topologically disordered systems is examined. A review of recent experimental evidence, relating to the shape of the density of states, is given.

## I. INTRODUCTION

In the tight-binding approach to the electronic properties of amorphous semiconductors such as a-Si, one can distinguish two aspects of the lack of long-range order that characterizes these materials. First there is the random variation in the size of matrix elements which represent interactions between neighboring orbitals. Second there is the random character of the topological network defined by the bonds between neighboring sites. The present paper concludes a series  $^{1,2}$  of three in which the topological aspect of disorder is treated in isolation by defining a simple model Hamiltonian, appropriate to amorphous Si or Ge, in which only nearest-neighbor interactions are considered and the variation in the size of the interactions is neglected. The model, which is described more fully in the first two papers of this series, <sup>1,2</sup> can have

no pretension to anything like a complete description of an amorphous semiconductor. It merely elucidates the relationship between band structure and topological properties.

The previous papers<sup>1,2</sup> were chiefly devoted to the demonstration that, for such a model, various properties of the density of states are independent of the details of structure, provided that it is everywhere tetrahedrally coordinated, so they obtain for periodic and nonperiodic systems alike. These include the existence of a gap in the density of states, <sup>1-3</sup> the attainment of various bounds, <sup>1,2</sup> and the existence of two  $\delta$  functions in the density of states.<sup>1,2</sup> (If the overlap parameters  $V_1$  and  $V_2$ are given values appropriate to Si or Ge, the gap is between valence and conduction bands and the  $\delta$ functions are at the top of each band.<sup>4,5</sup>) The purpose of the present paper is to consider properties that are *not* independent of the structure. These